

100

Deposit barrier layer on contact hole sidewalls, over native oxide layer situated over silicide layer at bottom of contact hole, and over dielectric layer.

Remove portion of barrier layer and native oxide layer situated at bottom of contact hole to expose silicide layer.

Fig. 1

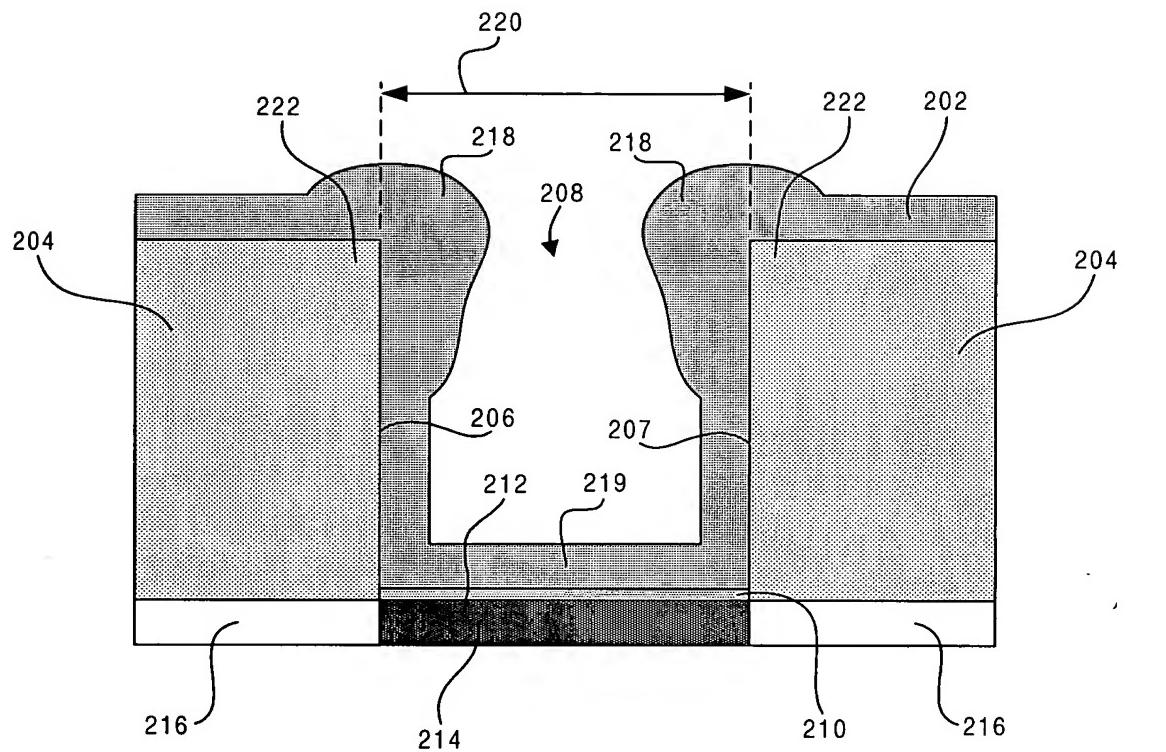
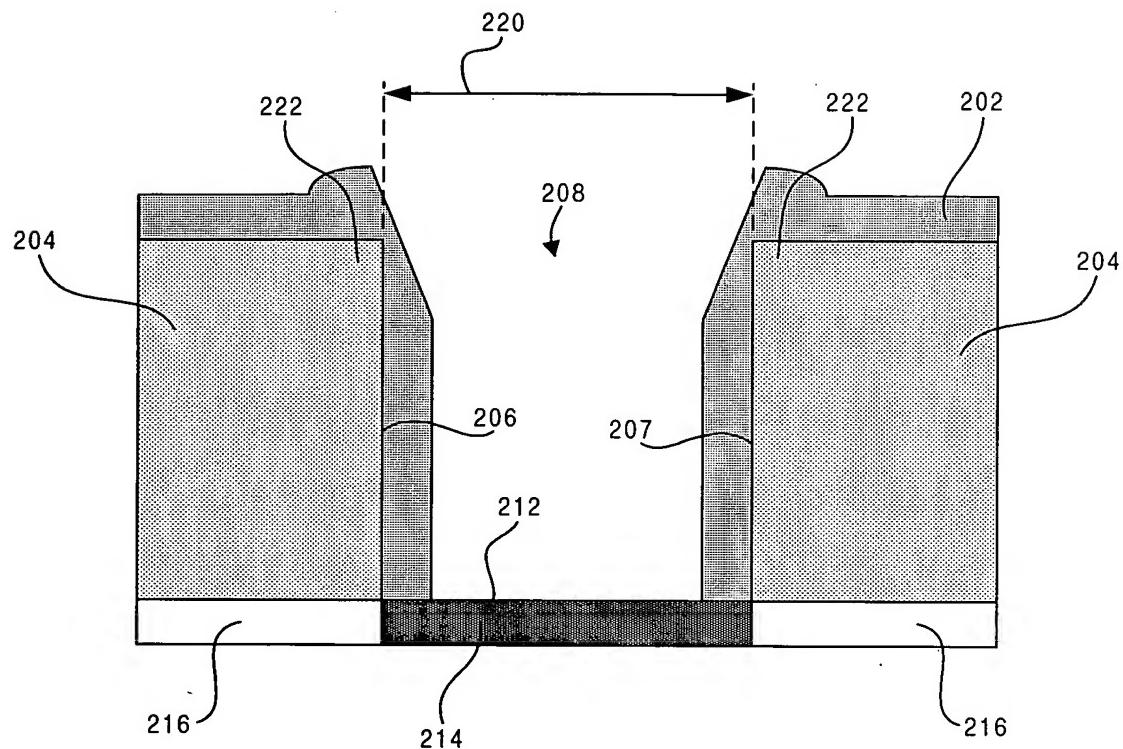


Fig. 2A

252

**Fig. 2B**

300

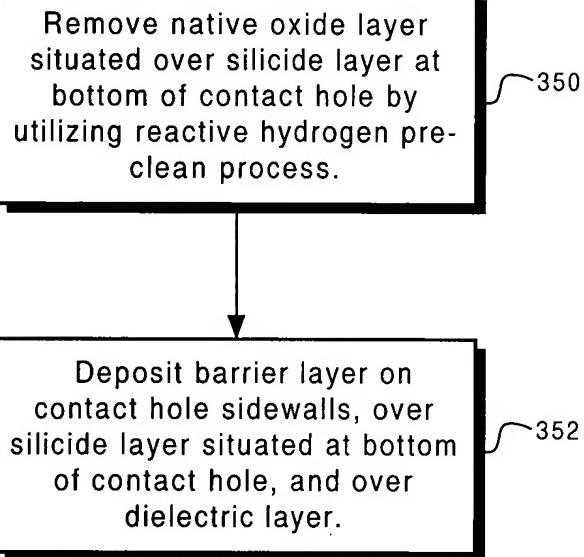


Fig. 3

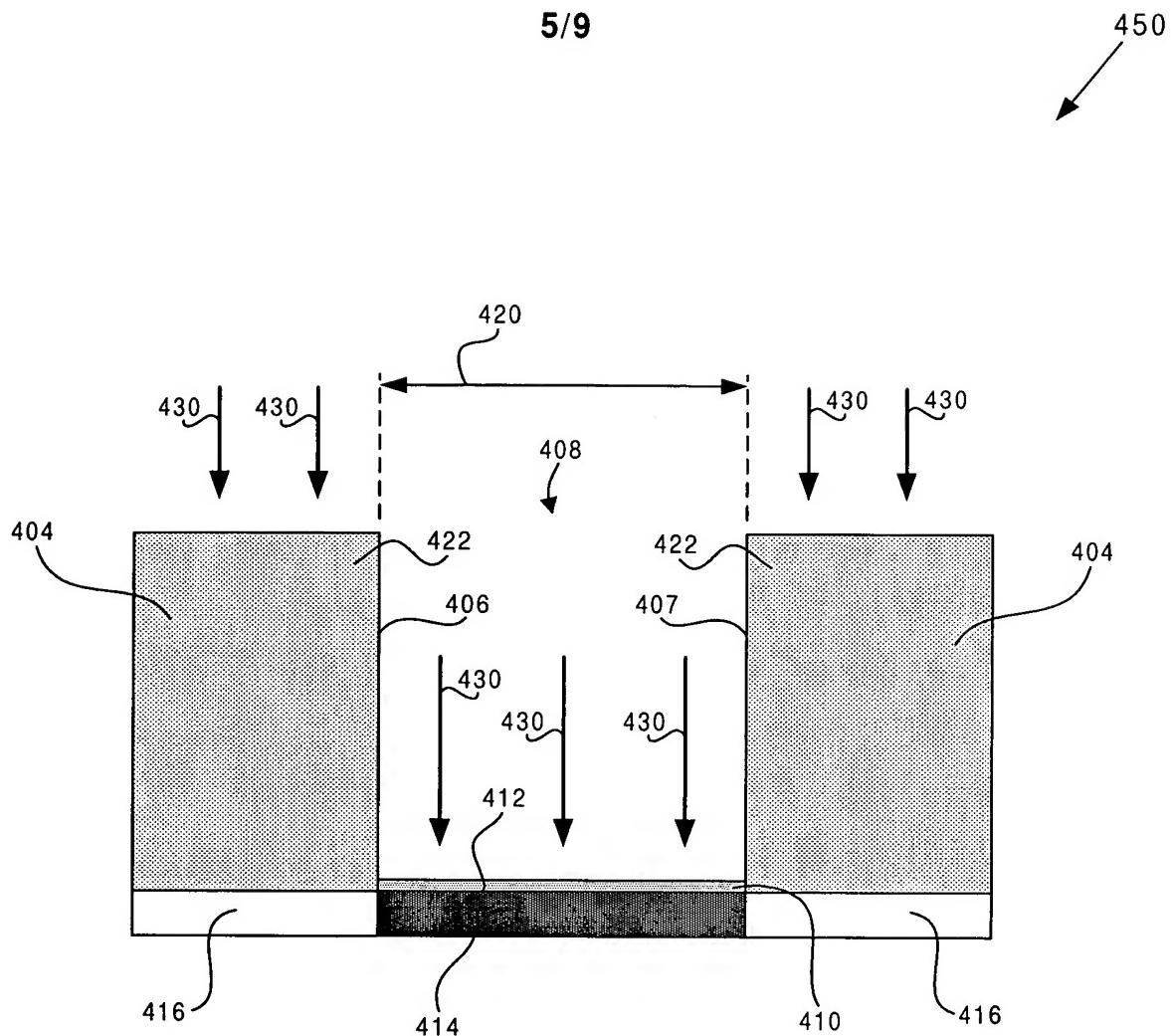


Fig. 4A

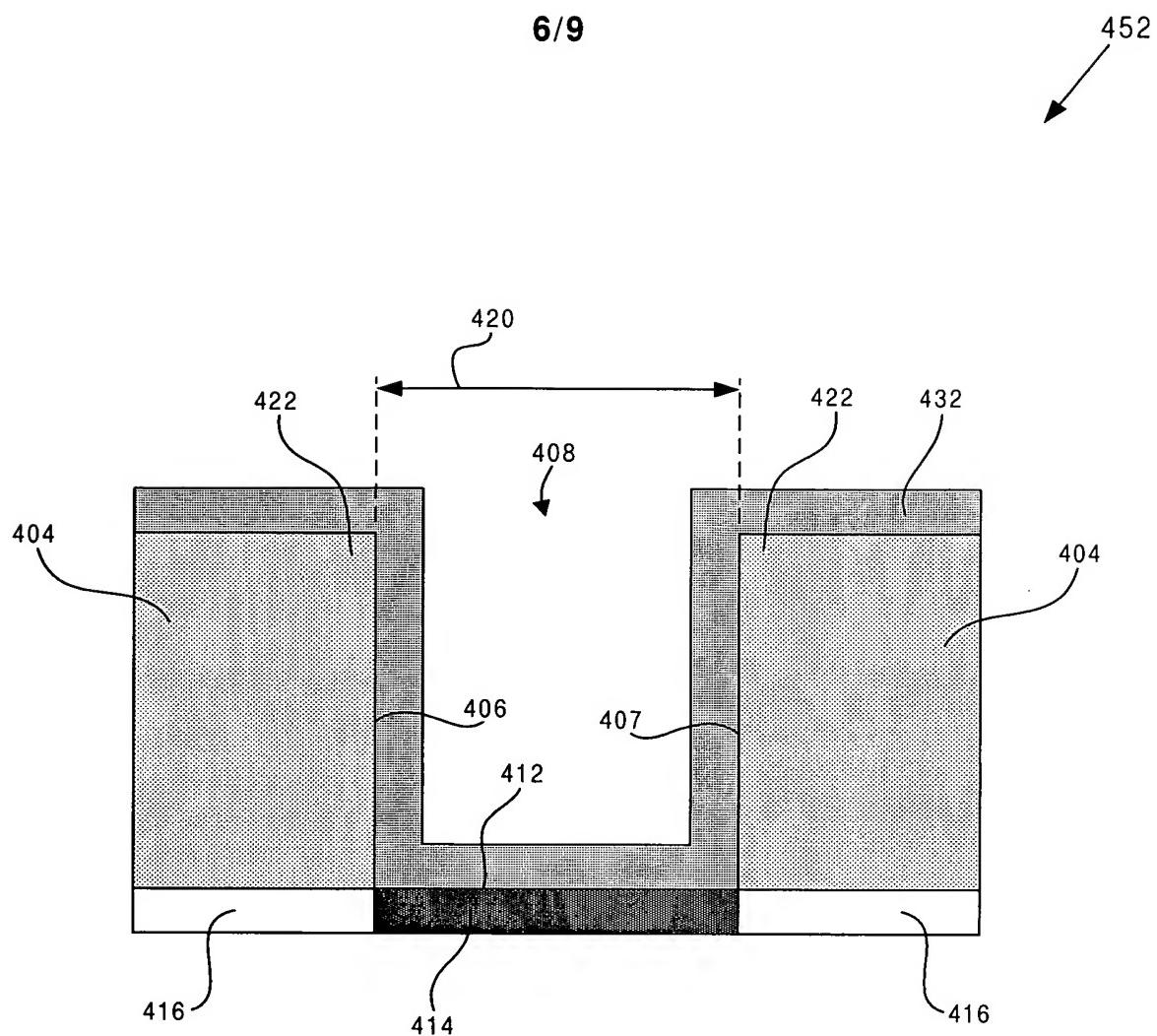


Fig. 4B

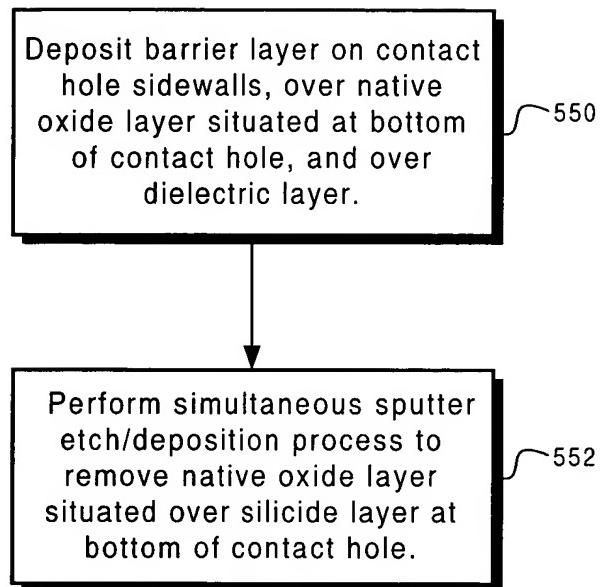


Fig. 5

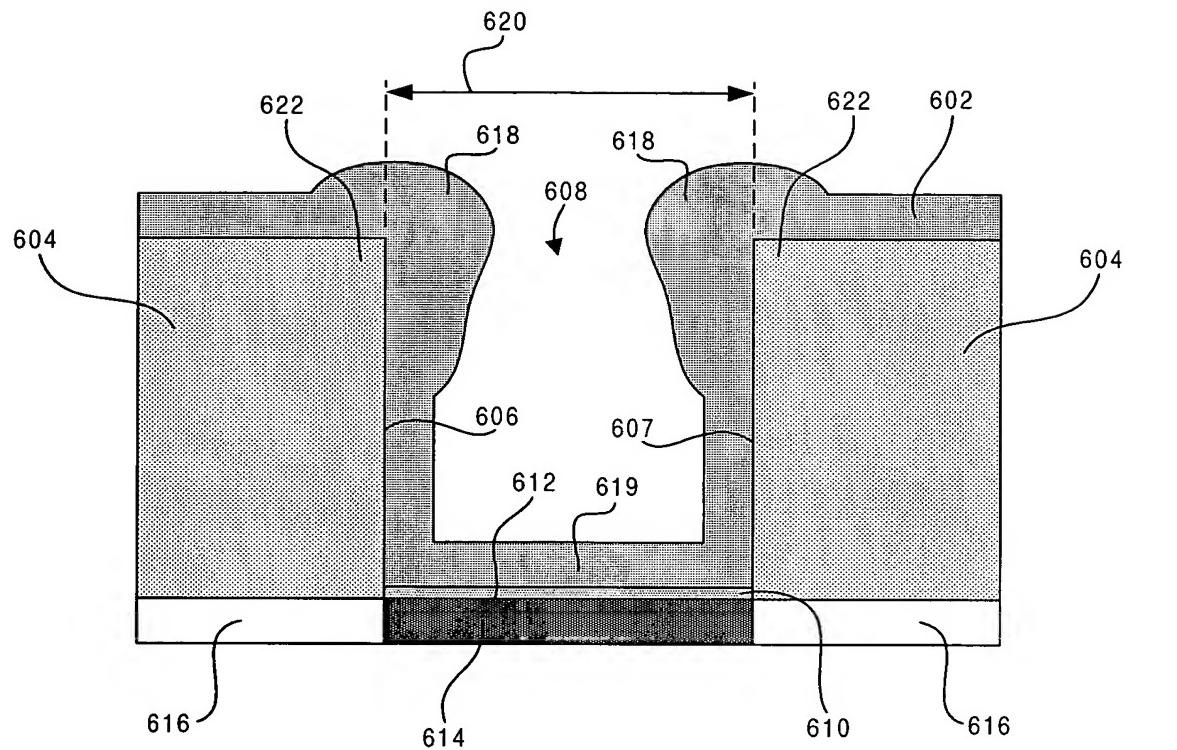


Fig. 6A

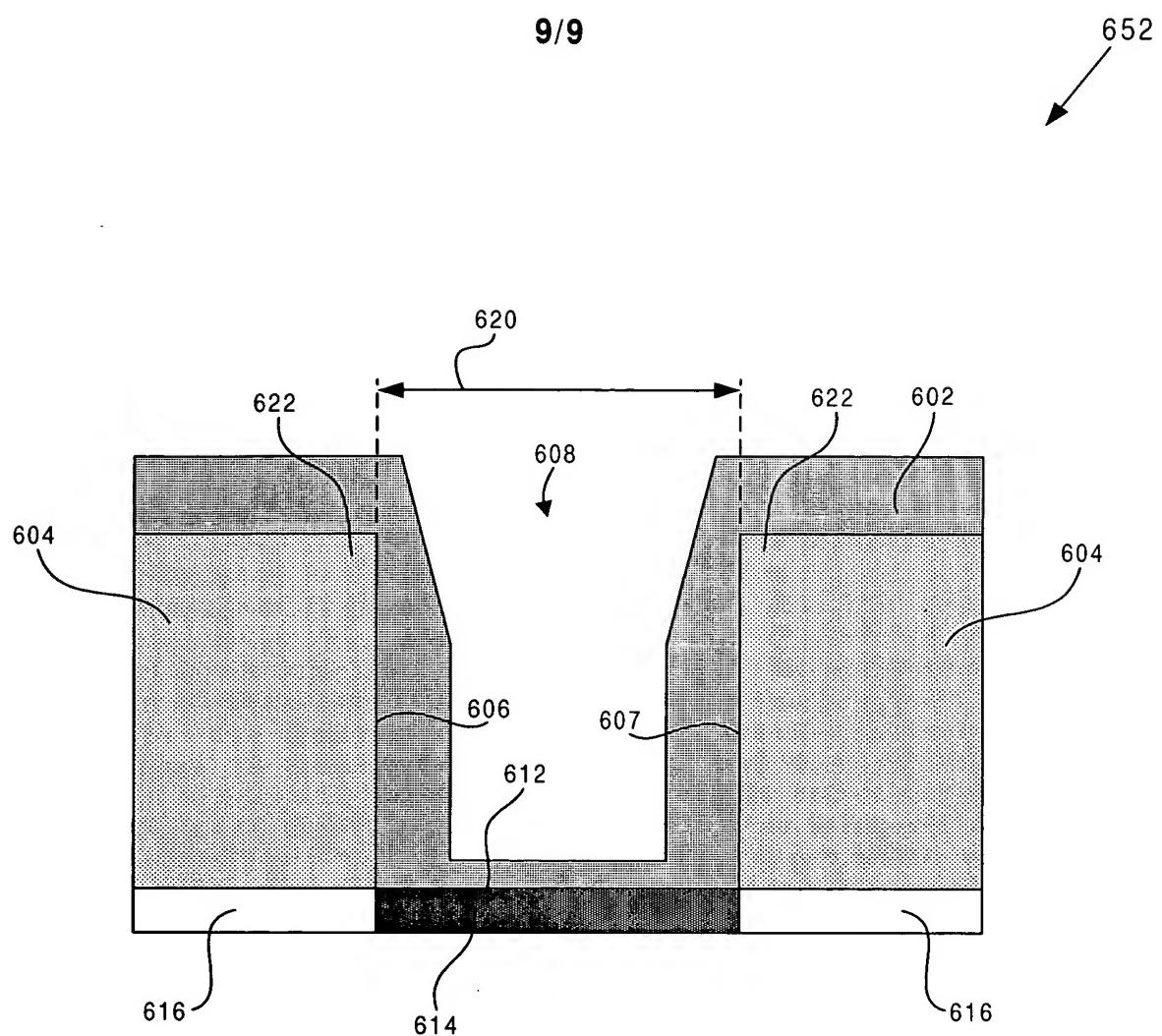


Fig. 6B